

ABSTRACT

[0037] The invention is directed to an arrangement for debris reduction in a radiation source based on a plasma, particularly for generating bundled radiation in the extreme ultraviolet (EUV) spectral region. The object of the invention, to find a novel possibility for beam shaping and debris reduction in a radiation source based on a plasma which substantially increases the life of collector optics without having to tolerate a substantial reduction in transparency or a sudden destruction of the protective mechanism, is met according to the invention in that exchangeable additional optics are arranged in the radiation path between a conventional debris filter and the collector optics, wherein a distance-increasing intermediate imaging of the source location relative to the collector optics is provided by the additional optics for further debris reduction.